

METHOD FOR MANUFACTURING SEMICONDUCTOR STRUCTURE

ABSTRACT

Embodiments of the disclosure relate to the technical field of semiconductors, and provide a method for manufacturing a semiconductor structure. The method includes: providing a substrate; forming a semiconductor layer on the substrate; performing P-type doping on the semiconductor layer to transform the semiconductor layer into an initial mask layer; performing a first patterning treatment on the initial mask layer to form a mask layer having an opening; and performing a second patterning on the substrate by taking the mask layer as a mask and using an etching process. An etching rate of the substrate is greater than an etching rate of the mask layer during the etching process. The embodiments of the disclosure are at least beneficial to improve the precision of the patterning treatment on the substrate and the initial mask layer.

[Fig. 1]